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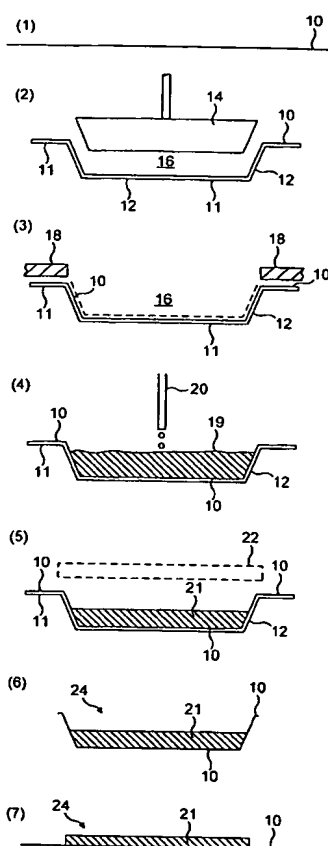
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(54) Title: **METHOD OF MANUFACTURING GAS DIFFUSION ELECTRODES**

(57) Abstract: A process is described for manufacturing gas diffusion electrodes, which process comprises: (a) treating an area of a pre-shrunk porous hydrophobic substrate so as to restrict the slurry deposited in step b) to the said area, preferably by forming a well in the area and/or treating the substrate in the area to render it less hydrophobic, e.g. by plasma treating the area; (b) dispensing a slurry of catalyst onto the said area, (c) removing liquid from the dispensed slurry, (d) treating the dried slurry to remove organic materials and (e) cutting the catalyst and the underlying portion of substrate from the rest of the substrate.

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